JUN 0 7 2006

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| <b>&amp;</b> /   |                         |
|--|-------------------------|
| plication Serial No  | 10/636,038              |
| Filing Date  |                         |
| Confirmation No  | 9972                    |
| Inventor   | Gurtej S. Sandhu        |
| Assignee   | Micron Technology, Inc. |
| Group Art Unit   | 1762                    |
| Examiner   | Eric B. Fuller          |
| Attorney's Docket No   | MI22-2194               |
| Customer No  | 021567                  |
| Title: Methods of Forming Material on a Substrate, and Method of Forming a |                         |
| Field Effect Transistor Gate Oxide on a Substrate                          |                         |

## RESPONSE TO MARCH 23, 2006 FINAL OFFICE ACTION PRELIMINARY AMENDMENT TO ACCOMPANY RCE FILING

To:

Mail Stop RCE

**Commissioner for Patents** 

P. O. Box 1450

Alexandria, VA 22313-1450

VIA U.S. EXPRESS MAIL

From:

Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)

Wells St. John P.S.

601 West First Avenue, Suite 1300

Spokane, WA 99201-3828

Responsive to the Final Office Action dated March 23, 2006, Applicant amends and remarks as follows:

## <u>AMENDMENTS</u>